

ABSTRACT

MASK SYSTEM EMPLOYING SUBSTANTIALLY CIRCULAR OPTICAL PROXIMITY CORRECTION TARGET AND METHOD OF MANUFACTURE THEREOF

5 A method of manufacture of a mask system includes: providing design data;
generating a substantially circular optical proximity correction target from the design data;
biasing a segment of the substantially circular optical proximity correction target; and
generating mask data based on the shape produced by biasing the segment of the substantially
circular optical proximity correction target.

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Fig. 1